

Tuning refractive index sensing properties of micro-cavity in-line Mach-Zehnder interferometer with plasma etching

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ABSTRACT

This work presents an application of reactive ion etching (RIE) for an effective tuning of the spectral response and the refractive-index (RI) sensitivity of the micro-cavity in-line Mach-Zehnder interferometer (μ IMZI). The μ IMZIs were fabricated using femtosecond laser micromachining in a standard single-mode fiber as a form circular holes with a diameter of 54 μ m. The application of RIE with SF₆ and O₂ used as reactive gas allows for an efficient and well-controlled etching of the fabricated structure. The process resulted in cleaning the bottom of the micro-cavity and smoothing of its sidewalls. In transmission measurements, the effect of the plasma processing was observed as an increase in both spectral depths of the minima and RI sensitivity of the structure, as well as improved wettability of the micro-cavity surface, which made the measurements faster and easier.

Keywords: optical fiber sensors, refractive index sensing, Mach-Zehnder interferometer (MZI), microstructure fabrication, femtosecond laser micromachining, refractive ion etching (RIE), plasma processing

INTRODUCTION

The concept of Mach-Zehnder interferometer is very well known and there are many ways to implement it in a fiber [e.g. 1,2,3]. When the interferometer is supposed to be used for sensing purposes, especially for determination of properties of liquids, typically a cavity needs to be formed in a fiber. Out of many available methods for cavity fabrication, femtosecond (fs) laser micromachining where extremely short laser pulses with high peak power are applied, offers many advantages, which includes negligible heating of the beam-exposed area resulting in very little damage in the working area and ability to produce small, well-defined shape on and in the fiber. That is why a fs laser system was recently used to fabricate several micro-cavity in-line MZI (μ IMZI) structures [4,5]. The light propagating through the fiber core splits at the cavity sidewall [6]. Both parts of the light, penetrating the cavity and the other, undisturbed in the core, interfere at the other sidewall. When the liquid sample fills the cavity, the sensing path leads through it. Depending on properties of liquid, i.e., its refractive index (RI), the interference take place differently. Besides advantages of μ IMZI structure such as portability, high sensitivity and the possibility to measuring very small volumes of liquid, there are also some challenges. A very small size of the cavity makes its cleaning difficult. The small pieces of glass remain after the fabrication process and can reduce the volume of the cavity as well as the area of the sensing surface, which in turn can affect the RI sensitivity. What is more, there is a problem with a filling of the cavity, especially with high-density liquids. Any increase in wettability of the cavity surface would allow for faster, more repeatable and accurate measurements.

Etching of the optical fiber cladding has already been applied for enhancing the RI sensitivity of optical fiber sensors. There are two techniques which are widely used, namely those using liquid etchants (e.g., wet etching in HF acid [7, 8]) or vapor-based etchants, i.e., plasma etching [9, 10, 11]. In this work, we used reactive ion etching (RIE) where in addition to chemical etching, the particles are accelerated towards the sample surface and physically remove the material by an ion bombardment on material's surface [12]. As etching reagents typically fluorides, e.g. SF₆ or CF₄, are used. In fluorine forming plasmas, the F atoms are principal etchant, but also is well known that the addition of oxygen can increase the etch rate [13]. Oxygen has a dual role in this process: enhances the production of the etchant, F atoms and occupies the active silicon etch site, which retards the etching reaction but significantly increases the hydrophilicity of the surface.

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The plasma processing is also accurate, more precise than any wet etching process, especially when narrow trenches are processed (e.g., [7]) and in contrast to chemical reagents, nontoxic and noncorrosive. Might be especially convenient for modification of as small cavities as a couple of picoliters in volume. In this paper, we exposed to RIE a μ IMZI structure, which in comparison to earlier reported works, is fabricated as a circular hole (Fig.1). The structure was fabricated solely with a femtosecond laser, and then modified with SF₆ and O₂ plasma-based post-processing, aiming for improving the wettability of the structure sidewalls, clean and better define the flat bottom of the micro-cavity and in consequence increase the overall sensitivity of the sensor.

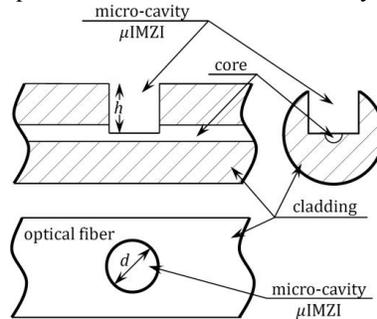


Figure 1. Schematic representation of the μ IMZI.

METHODOLOGY

2.1 Manufacturing of the μ IMZI structures

Structures in the form of cylindrical holes were fabricated in standard Corning SMF28 fibers. The micromachining process was performed using a Solstice Ti:Sapphire fs laser operating at $\lambda = 795$ nm. The fiber was irradiated by 82 fs pulses. The system was working with a repetition rate of 10 kHz. In order to make the micro-cavity, the laser beam was directed into a suitably designed micromachining setup based on the Newport μ Fab system. The system was equipped with a 20x lens, with NA = 0.30. Fiber transmission was monitored during the process with an NKT Photonics SuperK COMPACT supercontinuum white light source and a Yokogawa AQ6370C optical spectrum analyzer. The fabrication process was controlled with software developed in-house.

2.2 Plasma etching

The RIE process has been performed using Oxford PlasmaPro NGP80 system. The plasma obtained with the SF₆ flow of 30 sccm and O₂ flow of 100 sccm, pressure 100 mTorr and power 250 W. The temperature during the processes was set to 20°C and each etching was 3 min.-long.

2.3 μ IMZI analysis

The optical transmission of the μ IMZI for the refractive index sensitivity measurement was, as well as in the case of micromachining, monitored in the spectral range of 1100-1700 nm using a broadband laser light source NKT Photonics SuperK COMPACT and an optical spectrum analyzer Yokogawa AQ6370C. The set of water/glycerin solutions whose n_D varied in the range of 1.3333-1.4000 RIU was used to perform the sensitivity measurements of the μ IMZIs. The n of the solution was measured using a digital refractometer VEE GEE PDX-95 as a reference.

RESULTS

The structure with diameter $d = 54$ μ m was chosen to illustrate the effect of etching on properties of μ IMZI. The sample underwent four consecutive 3-min.-long etching processes. The transmission spectra after each process when the micro-cavity was filled with water is shown in Fig. 2. Comparison of spectra reveals that the etching is well observed in the case of a μ IMZI structure in terms of the depth of minimum in the spectrum (by over 10 dB), while barely noticeable in terms of minima shift. The transmission spectra of the samples for the n varying from 1.3333 to 1.4000 RIU in the micro-cavities before and after plasma post-processing are shown in Fig. 3a and 4a respectively. In Fig. 3b and 4b, the corresponding spectral locations of minima are plotted for various n . The points corresponding to each minimum are linearly approximated with the least squares method and the values of sensitivity in different n regions. The sensitivity is designated by a shift of minima in transmission spectra caused by aqueous solutions with various n filling the micro-cavity. It can be seen that the etching process affected the spectra and had a significant impact on the overall RI sensitivity. As it is depicted in Fig. 4b, in comparison to Fig. 3b, the sensitivities after plasma post-processing in both the RI ranges, namely

1.3333 to 1.3500 RIU and $n = 1.3600$ to 1.3900 RIU, are higher than before plasma treatment and reach over 12,000 and 15,000 nm/RIU, respectively. Also, the traced minima in the μ IMZ spectrum look smoother and more pronounced (Fig. 4a).

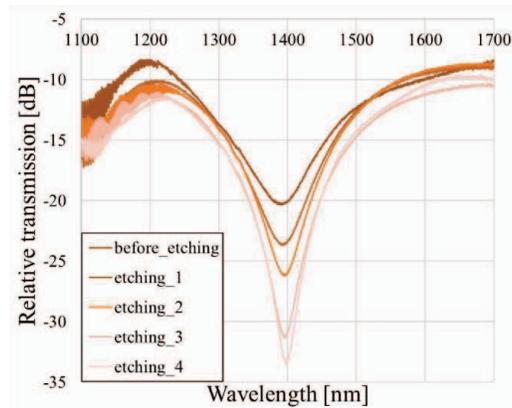


Fig. 2. The effect of each consecutive etching process on the μ IMZI transmission spectra when water filled the micro-cavity.

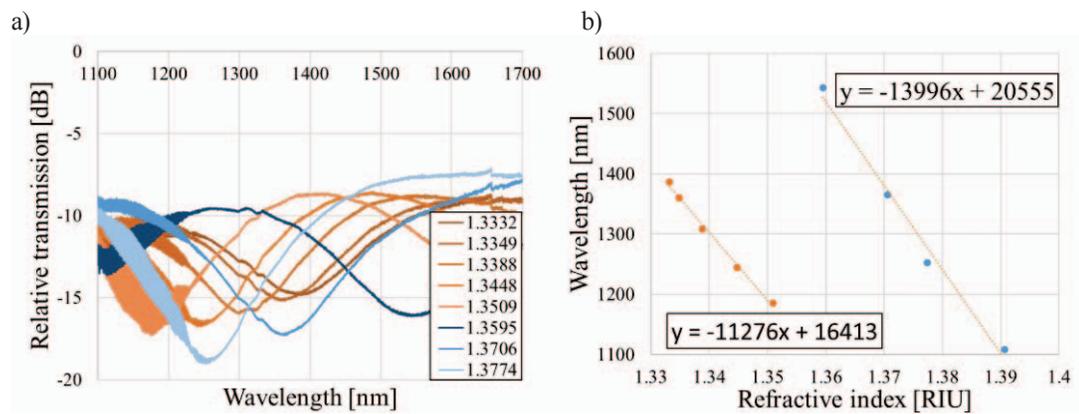


Fig. 3. Spectral response (a) and transmission minimum wavelength (b) of the μ IMZI before the plasma etching for aqueous solutions in the micro-cavity with n ranging from 1.33 to 1.40 RIU.

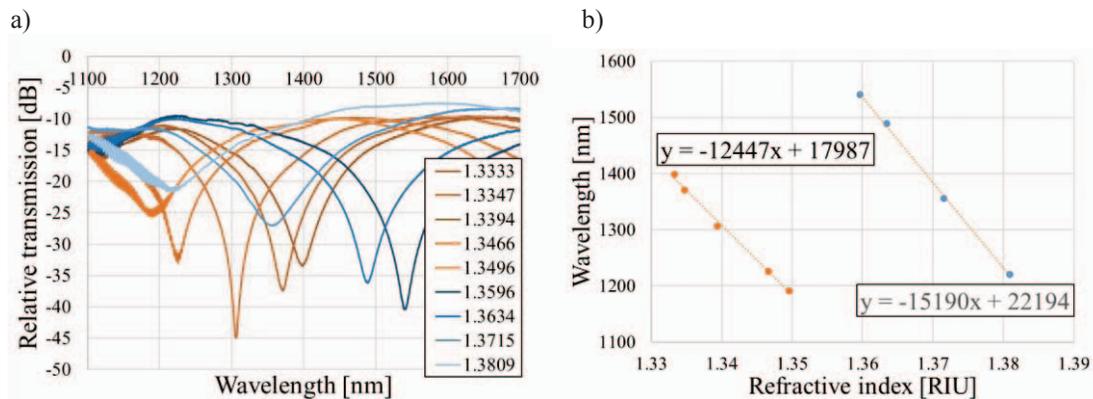


Fig. 4. Spectral response (a) and transmission minimum wavelength (b) of the μ IMZI after all the plasma etching processes for aqueous solutions in the micro-cavity with n ranging from 1.33 to 1.40 RIU.

It must be also noted that the surface after plasma treating was much more hydrophilic than before any processing. The effect enabled for easier introduction of the liquid into the micro-cavity, especially those with higher refractive indices. Furthermore, we have found that plasma-based etching used for micro-cavity processing is much more precise than earlier reported wet etching with HF acid [4]. The process described here did not cause any further uncontrolled etching of the surface and is strictly controlled by process time.

Additionally, we have obtained good cleaning the cavity surface which is very important, since the residual material in form of glass scarps does not disturb the further measurements. This issue might have a crucial impact on the accuracy and repeatability of the further measurements.

CONCLUSIONS

In this paper, we have demonstrated a highly sensitive refractive index sensor, based on a micro-cavity in-fiber Mach-Zehnder interferometer. It was fabricated with a femtosecond laser and then underwent plasma post-processed. The processing resulted in a well-visible increase in the spectral depth of the interference minima, what made the minima wavelength highly defined for any measurements. The process also had an impact on refractive index sensitivity which was increased to over 15 000 nm/RIU. What is more an application of RIE for hydrophilization of the surface allows for the effective introduction of the liquid into the micro-cavity. The obtained improvements in functional properties of the interferometers allow for their future applications for investigations on sub-nanoliter volumes of liquids.

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